

## INFORMATION DISCLOSURE CITATION (Us several sh ets if n c ssary)

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Applicant	Katsuhiko HIEDA			• •	660		
Filing Date	July 30, 2001	Group					
	U.S	S. PATENT D	OCUMENTS				
Examiner Initial*	Document Number	Date	Name	Class	Sub Class	Filing Date If Appropriate	
TL	4,979,014	12/18/90	Hieda et al.				
T	5,466,621	11/14/95	Hisamoto et al.				
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	Document Number	Date	Country	Class	Sub Class	Translation Yes or No	
7L	6-9245	2/2/94	Japan			0Abstract	
TL	2582794	11/21/96	Japan			Abstract	
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